IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Hiroyuki FUKUYAMA et al. Conf.:

Appl. No.: New Group:

Filed: March 26, 2004 Examiner:

For: SINGLE CRYSTALLINE ALUMINUM NITRIDE

FILM, METHOD OF FORMING THE SAME, BASE SUBSTRATE FOR GROUP III ELEMENT NITRIDE FILM, LIGHT EMITTING DEVICE AND SURFACE

ACOUSTIC WAVE DEVICE

INFORMATION DISCLOSURE STATEMENT
(SUBMISSION WITH CONTINUATION-IN-PART OR
RULE 1.53(b) CONTINUATION OR DIVISIONAL APPLICATION)

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

March 26, 2004

Sir:

Pursuant to 37 C.F.R. §§ 1.97 and 1.98, Applicant(s) hereby submit(s) an Information Disclosure Statement for consideration by the Examiner.

I. LIST OF PATENTS, PUBLICATIONS OR OTHER INFORMATION

The patents, publications, or other information submitted for consideration by the Office are listed on the PTO-1449 form(s), attached hereto.

II. REFERENCES PREVIOUSLY CITED OR SUBMITTED

Pursuant to 37 C.F.R. § 1.98(d), consideration of information listed on the PTO-1449 form(s) is requested since any patents, publications, or other information which are listed on the PTO-1449 form(s) but for which copies are not enclosed herewith, were previously cited by or submitted to the PTO in one of the following applications which has been relied upon for an earlier filing date under 35 U.S.C. § 120:

<u>U.S. Appl. No(s).</u> 10/247,539 <u>U.S. Filing Date(s)</u> September 20, 2002

III. FEES

This Information Disclosure Statement is being filed concurrent with the filing of a continuation-in-part, continuation, or divisional patent application; therefore, no fee is required.

If the Examiner has any questions concerning this IDS or requires a copy of any of the references cited but not provided, he/she is requested to contact the undersigned. If it is determined that this IDS has been filed under the wrong rule, the PTO is requested to consider this IDS under the proper rule and charge the appropriate fee to Deposit Account No. 02-2448.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fee required under 37 C.F.R. §§ 1.16 or 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

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%5 MSW/TBS/mua 1691-0177PUS2 P.O. Box 747
Falls Church, VA 22040-0747
(703) 205-8000

Attachment(s):	\boxtimes	PTO-1449(s)			
	\boxtimes	References - (1) document			
		Foreign Search Report			
		Other:			

(Rev. 02/12/2004)

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